

PATENT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

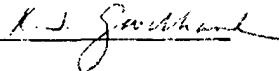
Applicants	Ishiduka, et al.	Examiner:	Johnson, Connie P.
Application No.:	10/591,718	Group Art Unit:	1795
Confirmation No:	3280	Docket:	1608-7 PCT/US/RCE
Filed:	September 5, 2006	Dated:	May 7, 2009
For:	POSITIVE-TYPE RESIST COMPOSITION FOR LIQUID IMMERSION LITHOGRAPHY AND METHOD FOR FORMING RESIST PATTERN		

Commissioner for Patents  
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Dated: May 7, 2009

Signature: K.J. Goodhand/ 

**AMENDMENT AND RESPONSE PURSUANT TO 37 C.F.R. §1.114**

Sir:

In response to the final Office Action dated February 10, 2009, the due date for which is May 10, 2009, please amend the above-identified application with the filing of a request for Continued Examination (RCE) as follows:

Amendments to the Claims begin on page 2 of this submission.

Remarks begin on page 9 of this submission.